

AS removed by H_2SO_4 , for instance. The wafer can be inserted into it and, subsequently, be dried, or the wafer can be exposed to the primer being in a gaseous state.

Please replace the paragraph beginning at page 16, line 18, with the following rewritten paragraph:

AS The use of photosensitive resist tips with larger bending radius and/or certain edge angles can be necessary for other applications than scanning probe microscopy, for example for profile meters or measuring scanners for certain purposes. This has been mentioned above. It should be possible without problems for one trained in the art, in such cases to design the exposure masks accordingly and, in particular, to select the exposure angle such that the desired tip profile is created. It is also possible to further adjust the profile design by varying the photosensitive resist used for the given needs.
